

Title (en)

AN IN-SITU CHAMBER CLEAN PROCESS TO REMOVE BY-PRODUCT DEPOSITS FROM CHEMICAL VAPOR ETCH CHAMBER

Title (de)

IN-SITU-KAMMERREINIGUNGSVERFAHREN ZUR ENTFERNUNG VON NEBENPRODUKTLAGERUNGEN AUS EINER CHEMIKALIENDAMPFÄTZKAMMER

Title (fr)

PROCEDE DE NETTOYAGE IN SITU D'UNE CHAMBRE PERMETTANT D'ELIMINER DES DEPOTS DE SOUS-PRODUIT D'UNE CHAMBRE DE GRAVURE PAR VAPEUR CHIMIQUE

Publication

**EP 1831430 A2 20070912 (EN)**

Application

**EP 05854872 A 20051220**

Priority

- US 2005046226 W 20051220
- US 63789704 P 20041221
- US 13720005 A 20050524
- US 26616705 A 20051103

Abstract (en)

[origin: WO2006069085A2] A method and apparatus for cleaning a processing chamber comprising blocking a flow of cooling fluid to a channel within a support member within a processing chamber, elevating the support member to be within about 0.1 inches of a gas distribution plate, heating the gas distribution plate, and introducing a thermally conductive gas through the gas distribution plate into the processing chamber. In one aspect, the chamber comprises a chamber body and a support assembly at least partially disposed within the chamber body adapted to support a substrate thereon. The chamber further comprises a lid assembly disposed on an upper surface of the chamber body. The lid assembly includes a top plate and a gas delivery assembly which define a plasma cavity therebetween, wherein the gas delivery assembly is adapted to heat the substrate. A remote plasma source having a U-shaped plasma region is connected to the gas delivery assembly.

IPC 8 full level

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CPC (source: EP KR)

**B08B 7/00** (2013.01 - EP); **B08B 7/0035** (2013.01 - EP KR); **C23C 16/50** (2013.01 - KR); **C23C 16/503** (2013.01 - KR); **C23C 16/505** (2013.01 - KR); **C23C 16/511** (2013.01 - KR); **H01J 37/32009** (2013.01 - EP); **H01J 37/32357** (2013.01 - EP); **H01J 37/3244** (2013.01 - EP KR); **H01J 37/32522** (2013.01 - EP KR); **H01J 37/32862** (2013.01 - EP); **H01L 21/0262** (2013.01 - KR); **H01L 21/67207** (2013.01 - KR); **H01L 29/665** (2013.01 - EP); **H01L 29/6656** (2013.01 - EP); **H01L 29/6659** (2013.01 - EP); **H01L 29/7833** (2013.01 - EP)

Citation (search report)

See references of WO 2006069085A2

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